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WW Flack, G Newman, D Bernard, JC Rey, Y Granik, ... - Proc. SPIE, 1997 - ultratech.com
 ... pattern transfer operations such as dry **etching** and high ... information from each wafer,
 a special **reticle** with a ... 1) determination of the image of the **mask** at the ...

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Integrated device structure prediction based on model curvature - group of 2
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Y Granik, NB Cobb, FM Schellenberg - US Patent 6,643,616, 2003 - Google Patents
 ... (76) Inventors: **Yuri Granik**, 38838 Litchfield ... silicon yield is affected by several
 factors including **reticle**/maskpattern fidelity ... 20 resist and **etch** processing. ...

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Adoption of OPC and the Impact on Design and Layout - group of 17 »

FM Schellenberg, L Capodiec, B Socha - Proc. ACM/IEEE Design Automation Conf -
 doi.ieeecomputersociety.org

... by changing material properties or **etching** structures into the ... image corresponding
 to the modified **reticle** layout and ... polygons are added to the **mask** layout to ...

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Precision control of poly-gate CD by local OPC for elimination of microloading effect on 0.13-um ... - group of 5 »

MJ Li, S Maturi, P Dixit, DS Tucker, R Yang, H ... - spie.org
 ... systematic correction of these **distortions** by RET ... methodology that incorporates **lithographic** effects into a ... the dimensions resist effects, **etch** effects, **mask** ...

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Simulation for DUV-Lithography - group of 3 »

W Henke - Semiconductor Fabtech, 9th ed., Section - semiconductorfabtech.com
 ... resulting in an additional **pattern distortion** of resist ... ABOUT THE AUTHOR Wolfgang Henke received the Dipl ... He developed the **SOLID lithography simulator** and now ...
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Optimization of sub-100-nm designs for mask cost reduction

A Balasinski - Journal of Microlithography, Microfabrication, and ..., 2004 - link.aip.org
 ... These **distortions** cannot be completely corrected by **OPC** ... The author thanks Linard Karklin, Valery Axelrad ... correction, module 2: **Lithography simulation** based on ...
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TCAD development for lithography resolution enhancement - group of 5 »

LW Liebmann, SM Mansfield, AK Wong, MA Lavin, WC ... - IBM Journal of Research and Development, 2001 - research.ibm.com
 ... deliberate and proactive **distortion** of photomask ... of the **lithography** and **etch process**, significant lead ... necessary tradeoffs between **lithographic** enhancement and ...
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Integrating design data with manufacturing data: why you want to use a universal data model(UDM) - group of 5 »

WR Erck - Proceedings of SPIE, 2003 - si2.org
 ... Make sure designers use them 3. **Mask/Lithography/Wafer Etch** Models for ... and expanded by the author of this ... for optical and process **distortions** in manufacturing ...
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Phase shifting mask topography effect correction based on near-field image properties - group of 3 »

A Kroyan - US Patent 6,794,096, 2004 - Google Patents
 ... MOPC) Flow To Include **Mask Writer** Issues", IPCOM000009586D ... One advance in **lithography** called phase shifting is ... compensating for some litho-graphic **distortions**. ...
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Photomask Technology

MMMC Center - spie.org
 ... advances needed in the **mask writers**, inspection, metrology ... optimization and dry **etch** screening on ... 35 am: Chromeless phase **lithography reticle** defect inspection ...
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(book) Causal Analysis of Systematic Spatial Variation in Optical Lithography

H Zhang - 2002 - bcam.berkeley.edu
 ... variability of the plasma **etch process**, and that ... terms may cause image **distortion** or shifting ... of the most important sources of systematic spatial **lithography** ...
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Electron beam shot linearity monitoring

US Pat. 6721939 - Filed Feb 19, 2002 - Taiwan Semiconductor Manufacturing Co., Ltd
OPC applies systematic changes to mask geometries to **compensate** for the nonlinear **distortions** caused by optical diffraction and resist process effects. ...

Site control for OPC

US Pat. 7073162 - Filed Oct 31, 2003 - Mentor Graphics Corporation
To improve the pattern fidelity, changes can be made to the **mask/reticle** patterns that **compensate** for the expected optical **distortions**. ...

Lithographic apparatus, device manufacturing method, and device manufactured thereby

US Pat. 6809797 - Filed Mar 29, 2002 - ASML Netherlands B.V..
... 15 25 40 rotation of the **mask (reticle)**; 45 adjustment of the mask height (eg to **compensate** ... and the **lithographic** error LR asymmetry will be reduced. ...

Exposure apparatus and exposure method

US Pat. 6721033 - Filed Jul 13, 2000 - Nikon Corporation
Then at step S302 (masking step), a **mask (reticle)** having the designed pattern is formed. In step S303 (wafer fabrication step), wafers are produced from ...

Compact photoemission source, field and objective lens arrangement for high throughput electron beam lithography

US Pat. 6215128 - Filed Mar 18, 1999 - Etec Systems, Inc.
... and stages for supporting the substrate and the **mask (reticle)**. ... lenses of the photolithography subsystem can be used to **compensate** for distortion ...

Lithographic apparatus, device manufacturing method, and device manufactured thereby

US Pat. 6633366 - Filed Aug 10, 2001
Since these beam- **mask (reticle)**. Further improvement is impossible by short-lets only interfere in a small area, the Coulomb interaction ening the ...

METHOD OF MANUFACTURING A DEVICE BY EMPLOYING A LITHOGRAPHIC APPARATUS INCLUDING A SLIDING ELECTRON-OPTICAL ELEMENT

US Pat. 7102732 - Filed Apr 28, 2003 - Elith LLC
This decreases the Coulomb interaction and the chromatic aberration, which is large due to the plasmon losses in the **mask (reticle)**. ...

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Lithographic apparatus, device manufacturing method, and device manufactured thereby

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... and Monte Carlo simulation technique", Journal of Applied Physics 84(8), 1998, pp. ... which is large due to the plasmon losses in the mask (reticle). ...

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Thus, in effect, we are pre-compensating for the process distortions to come. ... Phase-shift method and optical process correction are implemented by ...

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stock based compensation. As a result, the GAAP estimates for earnings per share provided ... Calibre OPCverify, the new advanced optical process correction ...

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